

FIG.19
PRIOR ART

Title: METHOD OF MANUFACTURING A SEMICONDUCTOR
DEVICE CAPABLE OF ETCHING A MULTI-LAYER OF ORGANIC
FILMS AT A HIGH SELECTIVITY
Inventor(s): Hiroto OHTAKE, et al.
Filing Date: February 22, 2002
Serial No.: 10/080,848 Docket No.: KRM-00101

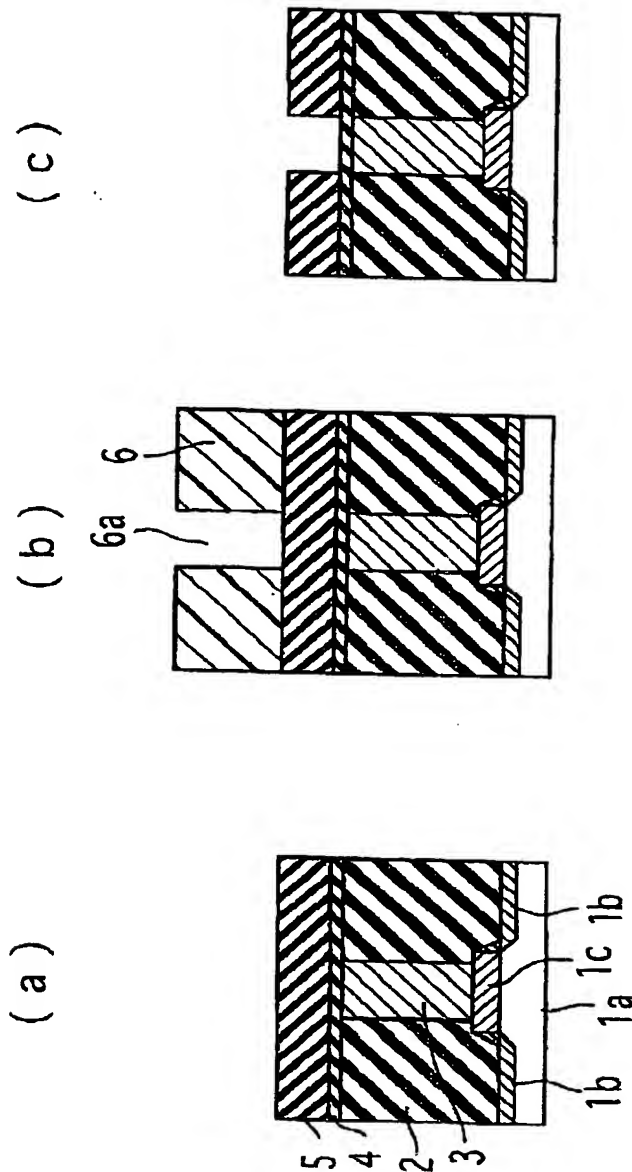


FIG.20
PRIOR ART

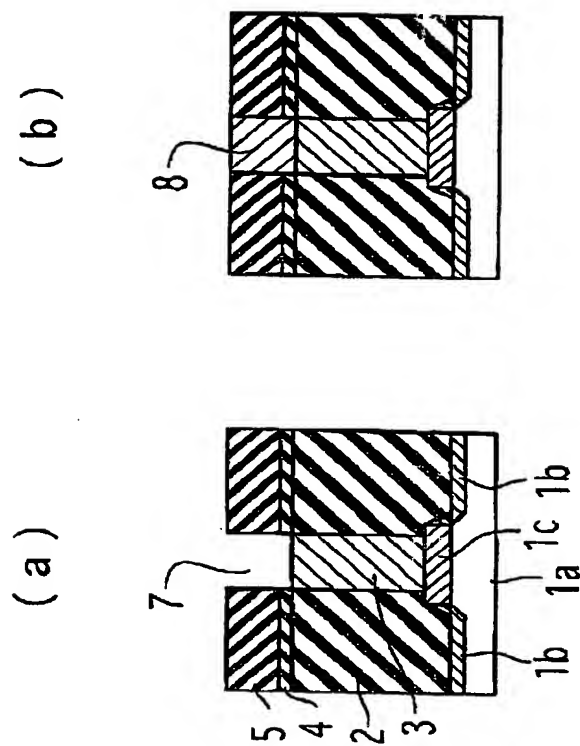


FIG.21
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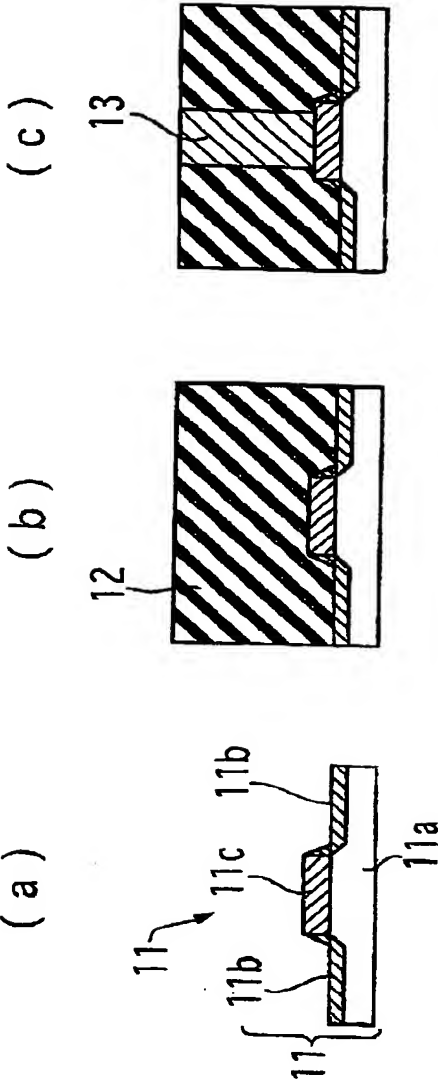


FIG.22
PRIOR ART

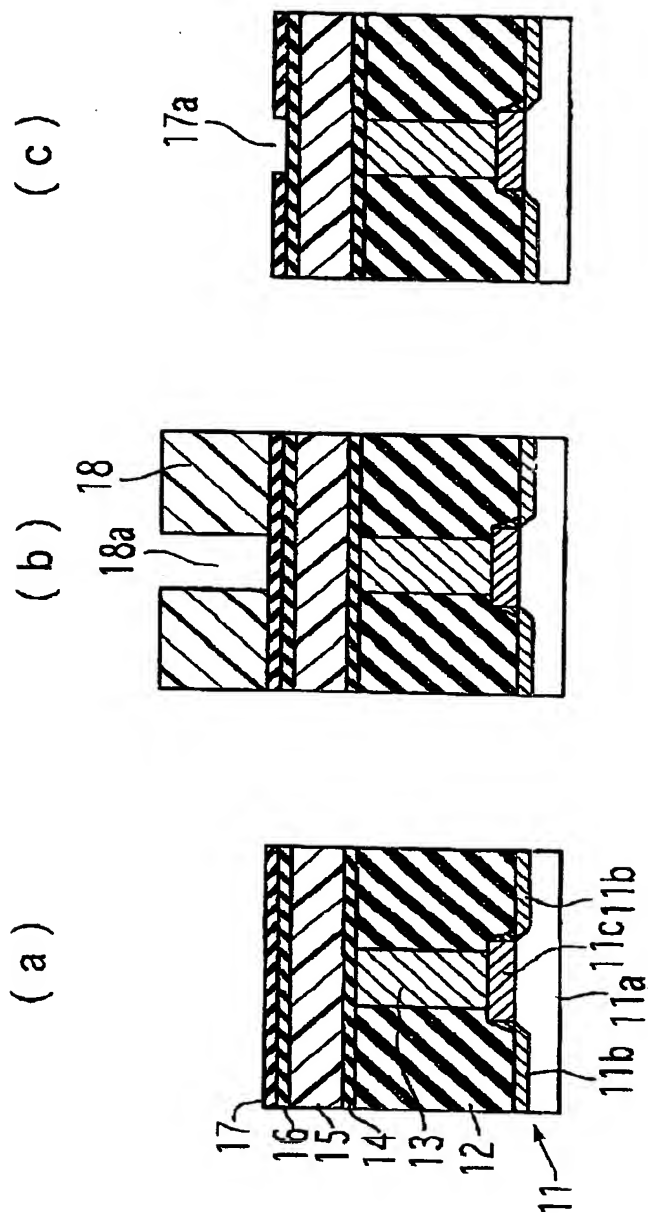


FIG. 23
 PRIOR ART

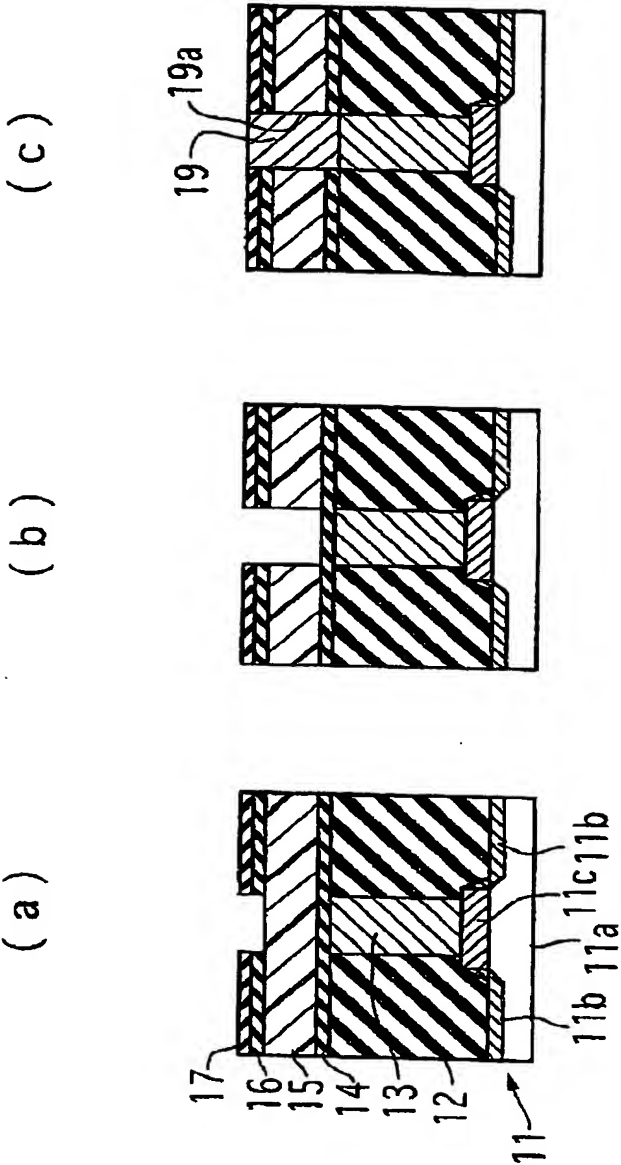


FIG.24
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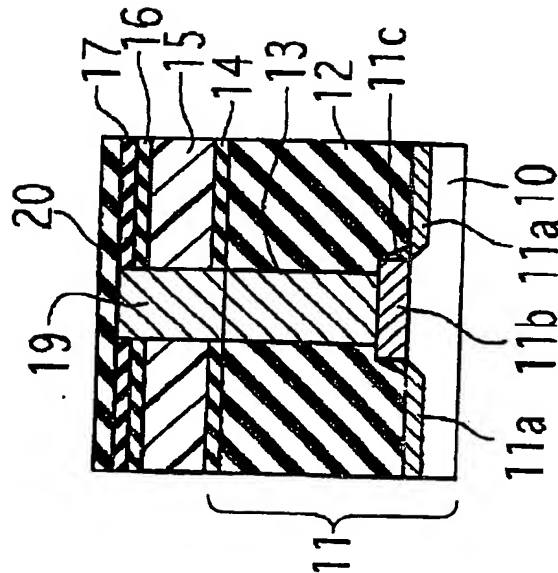


FIG. 25
PRIOR ART